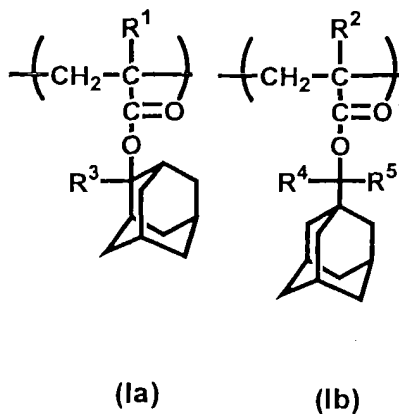


ABSTRACT

A chemical amplification type positive resist composition comprising:

(A) a resin which itself is insoluble or poorly soluble in an alkali aqueous solution but becomes soluble in an alkali aqueous solution by the action of an acid, and which contains a structural unit derived from p-hydroxystyrene and a structural unit represented by the formula (Ia) or (Ib)



wherein R¹ and R² each independently represents hydrogen or methyl, and R³ to R⁵ each independently represents alkyl having 1 to 8 carbon atoms; and

(B) radiation-sensitive acid generator comprising sulfonic acid ester of N-hydroxyimide compound; and onium salt is provided.